

Electronic Supplementary Information

**F-TiO<sub>2</sub>/P (VDF-HFP) hybrid films with enhanced dielectric permittivity and low dielectric loss**

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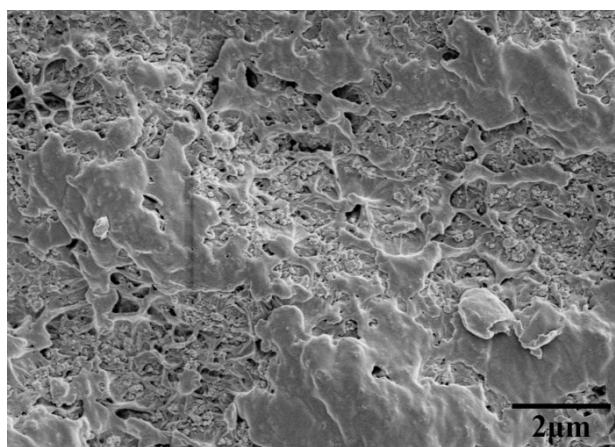


Fig. S1 High magnification SEM image of cross sections of composites with 20 vol % F-TiO<sub>2</sub> loading.

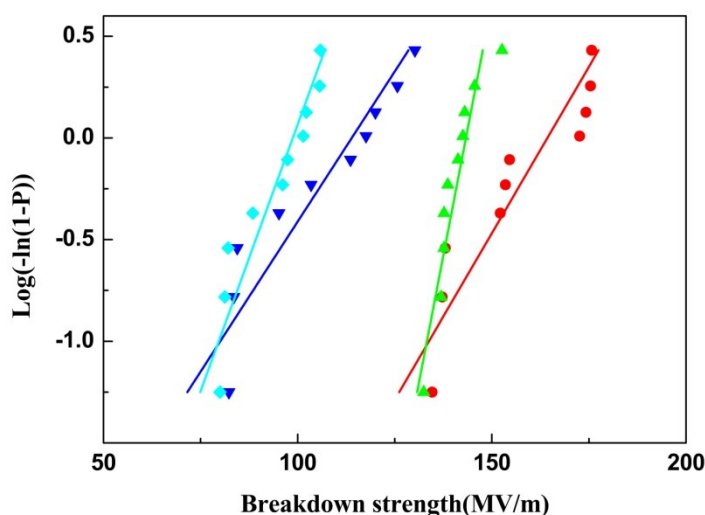


Fig. S2 Weibull plot of the breakdown strength of F-TiO<sub>2</sub>/ P(VDF-HFP) composites.

Tab. S1 Characteristic breakdown strength of F-TiO<sub>2</sub>/ P(VDF-HFP) composites.

Sample	5% F-TiO <sub>2</sub> /	10% F-TiO <sub>2</sub> / P(VDF-	15% F-TiO <sub>2</sub> / P(VDF-	20% F-TiO <sub>2</sub> / P(VDF-
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	<b>P(VDF-HFP)</b>	<b>HFP)</b>	<b>HFP)</b>	<b>HFP)</b>
<b>Breakdown strength</b>	163.17MV/m	143.50MV/m	113.54MV/m	98.78MV/m